

IN THE CLAIMS

Please amend Claim 13 as shown in marked-up form:

1. (Previously Presented) A device for the inspection of <sup>MM</sup> ~~one or~~  
~~more~~ a rotating surface (8) of a wafer (13), which device includes  
at least one light source (1), and a beam splitter (4) for  
splitting a light beam (2) that is emitted by said source into at  
least one reference beam (6) that is applied to a detector (16) and  
at least one measuring beam (5) that is applied to the surface  
(surfaces), the at least one measuring beam (5) containing at least  
one component in the direction of movement (U) of the relevant  
surface (8) or in the opposite direction, and the light (15) that  
is reflected by the surface (8) having, at least upon detection of  
a defect (14) on the surface (8), a frequency ( $\nu'$ ) that has been  
shifted relative to the at least one measuring beam (5) and that  
the at least one reference beam (6) can be superposed thereon,  
characterized in that the device includes an evaluation unit (29)  
for determining the velocity ( $\nu$ ) of a defect (14) on the surface  
(8) from the shifted frequency ( $\nu'$ ) and from this velocity the  
position of the defect on the surface (8).

2. (Original) A device as claimed in claim 1, characterized in  
that the detector (16) has exactly one entrance window that is